

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Masuda et al.
Appl. No. : 10/568,126
Filed : February 14, 2006
For : POSITIVE PHOTORESIST
COMPOSITION AND RESIST
PATTERN FORMATION
Examiner : Chu, John S Y.
Group Art Unit : 1752

OK TO ENTER: /JSC/

03/14/2008

RESPONSE TO OFFICE ACTION

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

In response to the Office Action mailed **December 5, 2007**, please consider the following remarks:

The listing of claims begins on page 2 of this paper solely for the Examiner's convenience. No amendments have been made.

Remarks/Arguments begin on page 4 of this paper.